

## EAST Search History

## EAST Search History (Prior Art)

| Ref # | Hits | Search Query  | DBs   | Default Operator | Plurals | Time Stamp          |
|-------|------|---|---|------------------|---------|---------------------|
| L2    | 375  | glass with substrate and roughness with (substrate or glass) and circuit\$4 and electroless and (electrodeposit\$4 or electroplat\$4)                                       | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | ON      | 2011/11/18<br>20:11 |
| L3    | 133  | glass with substrate and roughness with (substrate or glass) and circuit\$4 and electroless and (electrodeposit\$4 or electroplat\$4)and cataly\$4 with electroless         | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | ON      | 2011/11/18<br>20:13 |
| L4    | 25   | glass with substrate and roughness with (substrate or glass) with nm and circuit\$4 and electroless and (electrodeposit\$4 or electroplat\$4)and cataly\$4 with electroless | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | ON      | 2011/11/18<br>20:14 |
| S1    | 1    | 2002/0187267  | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | OFF     | 2011/07/26<br>14:20 |
| S2    | 1    | 2002/0187267  | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | ON      | 2011/07/26<br>14:20 |
| S3    | 2    | 10/580953   | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR               | ON      | 2011/07/26<br>15:21 |



|     |      |  |   |    |    |                     |
|-----|------|--|---|----|----|---------------------|
| S4  | 0    | (photosens\$4 or photoresist\$4)with novolak with patic\$4 with carbon   | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2011/07/26<br>15:25 |
| S5  | 0    | (photosens\$4 or photoresist\$4)with novolak with patic\$4 with absorp\$4  | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2011/07/26<br>15:25 |
| S6  | 0    | (photosens\$4 or photoresist\$4 or photo near resist\$4) with patic\$4 with absorp\$4                                  | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2011/07/26<br>15:25 |
| S7  | 0    | (photosens\$4 or photoresist\$4 or photo near resist\$4) with patic\$4 with convert\$4                                 | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2011/07/26<br>15:26 |
| S8  | 0    | (photosens\$4 or photoresist\$4 or photo near resist\$4) with patic\$4 with conver\$4                                  | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2011/07/26<br>15:26 |
| S9  | 3060 | (photosens\$4 or photoresist\$4 or photo near resist\$4) with absorp\$4  | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2011/07/26<br>15:26 |
| S10 | 1319 | (photosens\$4 or photoresist\$4 or photo near resist\$4) with absorp\$4 with light                                     | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2011/07/26<br>15:27 |
| S11 | 0    | (photosens\$4 or photoresist\$4 or photo near resist\$4) with absorp\$4 with light with ultra with novolak near2 epoxy | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2011/07/26<br>15:27 |



|     |    |   |   |    |    |                     |
|-----|----|---|---|----|----|---------------------|
| S12 | 0  | (photosens\$4 or photoresist\$4 or photo near resist\$4) with absorp\$4 with light with visible with novolak near2 epoxy  | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2011/07/26<br>15:28 |
| S13 | 0  | (photosens\$4 or photoresist\$4 or photo near resist\$4) with absorp\$4 near2 visible near light with novolak near2 epoxy | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2011/07/26<br>15:28 |
| S14 | 0  | (photosens\$4 or photoresist\$4 or photo near resist\$4) with absorp\$4 near2 visible with novolak near2 epoxy            | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2011/07/26<br>15:28 |
| S15 | 0  | (photosens\$4 or photoresist\$4 or photo near resist\$4) with absorp\$4 near2 visible near light with novolak             | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2011/07/26<br>15:29 |
| S16 | 0  | (photosens\$4 or photoresist\$4 or photo near resist\$4) with absorp\$4 near2 ultra with novolak                          | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2011/07/26<br>15:29 |
| S17 | 1  | (photosens\$4 or photoresist\$4 or photo near resist\$4) with absorp\$4 near2 ultra                                       | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2011/07/26<br>15:29 |
| S18 | 45 | (photosens\$4 or photoresist\$4 or photo near resist\$4) with novolak with absorp\$4                                      | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2011/07/26<br>15:30 |
| S19 | 0  | (photosens\$4 or photoresist\$4 or photo near resist\$4) with novolak with absorp\$4 with wave                            | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2011/07/26<br>15:30 |



|     |     |  |   |    |    |                     |
|-----|-----|--|---|----|----|---------------------|
| S20 | 20  | (photosens\$4 or photoresist\$4 or photo near resist\$4) with novolak with absorp\$4 with light  | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2011/07/26<br>15:30 |
| S21 | 0   | (photosens\$4 or photoresist\$4 or photo near resist\$4) with novolak with absorp\$4 with light and electroless                                    | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2011/07/26<br>15:30 |
| S22 | 0   | (photosens\$4 or photoresist\$4 or photo near resist\$4) with novolak with absorp\$4 with light and plating  | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2011/07/26<br>15:30 |
| S23 | 20  | (photosens\$4 or photoresist\$4 or photo near resist\$4) with novolak with absorp\$4 with light and pattern \$4                                    | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2011/07/26<br>15:30 |
| S24 | 129 | (photosens\$4 or photoresist\$4 or photo near resist\$4) with novolak with (carbon or metal) and pattern \$4                                       | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2011/07/26<br>15:35 |
| S25 | 1   | (photosens\$4 or photoresist\$4 or photo near resist\$4) with novolak with (carbon or metal)with(powder or particle or particulate) and pattern\$4 | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2011/07/26<br>15:35 |
| S26 | 213 | (photosens\$4 or photoresist\$4 or photo near resist\$4) with (carbon or metal)near (powder or particle or particulate) and pattern\$4             | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2011/07/26<br>15:36 |



|     |   |   |  |    |    |                  |
|-----|---|---|--|----|----|------------------|
| S27 | 0 | (photosens\$4 or photoresist\$4 or photo near resist\$4) with (carbon or metal)near (powder or particle or particulate)with absop \$4 and pattern\$4  | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2011/07/26 15:36 |
| S28 | 0 | (photosens\$4 or photoresist\$4 or photo near resist\$4) with (carbon or metal)near (powder or particle or particulate))and ((carbon or metal)near (powder or particle or particulate) with absop \$4 and pattern\$4  | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2011/07/26 15:37 |
| S29 | 0 | (photosens\$4 or photoresist\$4 or photo near resist\$4) with (carbon or metal)near (powder or particle or particulate))and ((iron) near(powder or particle or particulate) with absop\$4 and pattern\$4  | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2011/07/26 15:38 |
| S30 | 0 | (photosens\$4 or photoresist\$4 or photo near resist\$4) with (carbon or metal)near (powder or particle or particulate))and ((iron or metal or pigment or dye)near(powder or particle or particulate) with absop\$4 with (ultra or UV) and pattern\$4             | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2011/07/26 15:40 |
| S31 | 0 | (photosens\$4 or photoresist\$4 or photo near resist\$4) with (carbon or metal)near (powder or particle or particulate))and ((iron or metal or pigment or dye or carbon)near (powder or particle or particulate) with absop \$4 with (ultra or UV) and pattern\$4 | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2011/07/26 15:40 |



|     |   |  |   |    |    |                     |
|-----|---|--|---|----|----|---------------------|
| S32 | 0 | (photosens\$4 or photoresist\$4 or photo near resist\$4) with (carbon or metal)near (powder or particle or particulate))and ((iron or metal or pigment or dye or carbon)near (powder or particle or particulate) with absop \$4 with (ultra or UV)                   | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2011/07/26<br>15:40 |
| S33 | 0 | (photosens\$4 or photoresist\$4 or photo near resist\$4) with (carbon or metal)near (powder or particle or particulate))and ((iron or metal or pigment or dye or carbon)near (powder or particle or particulate) with absop \$4 with (infra or ir)                   | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2011/07/26<br>15:41 |
| S34 | 0 | (photosens\$4 or photoresist\$4 or photo near resist\$4 or novolak) with(carbon or metal)near(powder or particle or particulate))and ((iron or metal or pigment or dye or carbon)near (powder or particle or particulate) with absop \$4 with (infra or ir)          | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2011/07/26<br>15:41 |
| S35 | 0 | (photosens\$4 or photoresist\$4 or photo near resist\$4 or novolak) with(carbon or metal)near(powder or particle or particulate))and ((iron or metal or silver or pigment or dye or carbon)near(powder or particle or particulate) with absop \$4 with (infra or ir) | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2011/07/26<br>15:41 |



|     |   |   |   |    |    |                     |
|-----|---|---|---|----|----|---------------------|
| S36 | 0 | (photosens\$4 or photoresist\$4 or photo near resist\$4 or novolak) with(carbon or metal)near(powder or particle or particulate))and ((iron or metal or silver or pigment or dye or carbon)with(powder or particle or particulate) with absop\$4 with (infra or ir) | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2011/07/26<br>15:41 |
| S37 | 3 | photoresist with (pigment or dye)near3 absorb\$3 near3(UV or ultra) and (novolac or novolak)  | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2011/07/27<br>18:04 |
| S38 | 3 | photoresist with (pigment or dye)near3 absorb\$3 near3(UV or ultra) and (novolac or novolak)  | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2011/07/27<br>18:05 |
| S39 | 2 | 10/580953   | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2011/07/27<br>18:06 |
| S40 | 4 | (photoresist or photo near resist\$4 or photo near sensitive)with (pigment or dye or colorant)near3 absorb \$3 near3(UV or ultra) and (novolac or novolak)  | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2011/07/27<br>18:07 |
| S41 | 3 | (photoresist or photo near resist\$4 or photo near sensitive)with (pigment or dye or colorant)near3 absorb \$3 near3(ir or infra) and (novolac or novolak)  | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2011/07/27<br>18:08 |



|     |    |   |  |    |    |                  |
|-----|----|---|--|----|----|------------------|
| S42 | 26 | (photo lith\$4 or photoresist or photo near resist\$4 or photo near sensitive)same (pigment or dye or colorant)near3 absorb \$3 near3(UV or ultra) and (novolac or novolak)                       | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2011/07/27 18:10 |
| S43 | 41 | (photo lith\$4 or photoresist or photo near resist\$4 or photo near sensitive)same (pigment or dye or colorant)near3 absorb \$3 near3(UV or ultra or ir or infra) and (novolac or novolak)        | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2011/07/27 18:26 |
| S44 | 41 | (photo lith\$4 or photoresist or photo near resist\$4 or photo near sensitive)same (pigment or dye or colorant)near3 absorb \$3 near3(UV or ultra or ir or infra) and (novola\$2)                 | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2011/07/27 19:24 |
| S45 | 25 | (photo lith\$4 or photoresist or photo near resist\$4 or photo near sensitive)same (pigment or dye or colorant)near3 absorb \$3 near3(UV or ultra or ir or infra) and sulphone and ether and aryl | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2011/07/27 19:25 |
| S46 | 2  | 10/140761   | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2011/07/27 19:27 |
| S47 | 2  | 10/378553   | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2011/07/27 19:28 |



|     |     |   |  |    |    |                  |
|-----|-----|---|--|----|----|------------------|
| S48 | 408 | (photo lith\$4 or photoresist or photo near resist\$4 or photo near sensitive or novola\$4)same (pigment or dye or colorant)near3 absorb \$3 near3(UV or ultra or ir or infra)                          | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2011/07/27 19:32 |
| S49 | 189 | (photo lith\$4 or photoresist or photo near resist\$4 or photo near sensitive or novola\$4)with (pigment or dye or colorant)near3 absorb \$3 near3(UV or ultra or ir or infra)                          | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2011/07/27 19:32 |
| S50 | 0   | (photo lith\$4 or photoresist or photo near resist\$4 or photo near sensitive or novola\$4)with (pigment or dye or colorant)near3 absorb \$3 near3(UV or ultra or ir or infra)and metal near patten\$4  | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2011/07/27 19:32 |
| S51 | 12  | (photo lith\$4 or photoresist or photo near resist\$4 or photo near sensitive or novola\$4)with (pigment or dye or colorant)near3 absorb \$3 near3(UV or ultra or ir or infra)and metal near patter\$4  | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2011/07/27 19:33 |
| S52 | 12  | (photo lith\$4 or photoresist or photo near resist\$4 or photo near sensitive or novola\$4)with (pigment or dye or colorant)near3 absorb \$3 near3(UV or ultra or ir or infra)and metal near pattern\$4 | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2011/07/27 19:33 |



|     |    |  |   |    |    |                     |
|-----|----|--|---|----|----|---------------------|
| S53 | 13 | (photo lith\$4 or photoresist or photo near resist\$4 or photo near sensitive or novola\$4)with (pigment or dye or colorant)near3 absorb \$3 near3(UV or ultra or ir or infra)and (conductor or metal) near pattern\$4 | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2011/07/27<br>19:33 |
| S54 | 14 | (photo lith\$4 or photoresist or photo near resist\$4 or photo near sensitive or novola\$4)same (pigment or dye or colorant)near3 absorb \$3 near3(UV or ultra or ir or infra)and (conductor or metal) near pattern\$4 | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2011/07/27<br>19:35 |
| S55 | 22 | (photo lith\$4 or photoresist or photo near resist\$4 or photo near sensitive or novola\$4)same (pigment or dye or colorant)near3 absorb \$3 near3(UV or ultra or ir or infra)and plating                              | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2011/07/27<br>19:35 |
| S56 | 2  | "20050175824"  | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2011/07/29<br>15:24 |
| S57 | 2  | 10/580953  | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2011/11/15<br>13:43 |
| S58 | 14 | "3998602"  | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2011/11/15<br>13:57 |



|     |      |  |   |    |     |                     |
|-----|------|--|---|----|-----|---------------------|
| S59 | 2382 | ((427/99.5/) or (427/304/) or (427/504/) or (427/97.9/) or (427/437/) or (427/443.1/)).OCLS.   | USPAT; USOCR  | OR | OFF | 2011/11/15<br>14:02 |
| S60 | 254  | S59 and function\$4 and (polymeriz\$4 or crosslink\$4 or graft\$4)   | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | OFF | 2011/11/15<br>14:03 |
| S61 | 0    | S59 and function\$4 with intercat\$4 and (polymeriz\$4 or crosslink\$4 or graft\$4)  | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON  | 2011/11/15<br>14:03 |
| S62 | 14   | S59 and function\$4 with interact\$4 and (polymeriz\$4 or crosslink\$4 or graft\$4)  | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON  | 2011/11/15<br>14:04 |
| S63 | 3    | "20030132121"  | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON  | 2011/11/15<br>14:13 |
| S64 | 3    | "20030132121"  | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON  | 2011/11/17<br>13:11 |
| S65 | 1511 | circuit with(Print\$4 or board\$4)and (cataly\$4 or plarium or palladium)with electroless and (metal or copper or silver) with electroplating and adhes\$4 | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON  | 2011/11/17<br>13:26 |



|     |     |   |   |    |    |                     |
|-----|-----|---|---|----|----|---------------------|
| S66 | 529 | circuit near(Print\$4 or board\$4)and (cataly\$4 or platinum or palladium)with electroless and (metal or copper or silver) with electroplating and adhes\$4 with (cataly \$4 or platinum or palladium)                          | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2011/11/17<br>13:27 |
| S67 | 0   | circuit near(Print\$4 or board\$4)and (cataly\$4 or platinum or palladium)with electroless and (metal or copper or silver) with electroplating and adhes\$4 with (cataly \$4 or platinum or palladium)and functional near group | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2011/11/17<br>13:27 |
| S68 | 0   | circuit near(Print\$4 or board\$4)and (cataly\$4 or platinum or palladium)with electroless and (metal or copper or silver) with electroplating and adhes\$4 with (cataly \$4 or platinum or palladium)and functional near group | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2011/11/17<br>13:27 |
| S69 | 95  | circuit near(Print\$4 or board\$4)and (cataly\$4 or platinum or palladium)with electroless and (metal or copper or silver) with electroplating and adhes\$4 with (cataly \$4 or platinum or palladium)and functional near group | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2011/11/17<br>13:28 |



|     |    |   |   |    |    |                     |
|-----|----|---|---|----|----|---------------------|
| S70 | 66 | circuit near(Print\$4 or board\$4)and (cataly\$4 or platinum or palladium)with electroless and (metal or copper or silver) with electroplating and adhes\$4 with (cataly \$4 or platinum or palladium)and functional near group and copolymer | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2011/11/17<br>13:28 |
| S71 | 1  | 12/729634   | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2011/11/17<br>13:37 |
| S72 | 64 | "6756286"   | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2011/11/17<br>13:51 |
| S73 | 2  | "20030034869"   | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2011/11/17<br>13:56 |
| S74 | 19 | "2003013"   | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2011/11/18<br>12:41 |
| S75 | 3  | "20030132121"   | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2011/11/18<br>12:41 |
| S78 | 1  | electroless and electoplat\$4 and electroless with cataly \$4 with adhes\$4 and circuit\$4 near(board or integrat\$4)   | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2011/11/18<br>12:45 |



|     |   |   |   |    |    |                     |
|-----|---|---|---|----|----|---------------------|
| S79 | 1 | electroless and electroplat\$4 and cataly\$4 with adhes\$4 and circuit\$4 near(board or integrat\$4)  | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2011/11/18<br>12:47 |
| S80 | 6 | electroless and electroplat\$4 and cataly\$4 same adhes\$4 and circuit\$4 near(board or integrat\$4)  | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2011/11/18<br>12:48 |
| S81 | 4 | electroless and electroplat\$4 and cataly\$4 with electroless same adhes\$4 and circuit\$4 near(board or integrat\$4)   | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2011/11/18<br>12:49 |
| S82 | 4 | electroless and electroplat\$4 with copper and cataly\$4 with electroless and cataly\$4 with(Poly\$4 or adhes\$4) and circuit\$4 near(board or integrat\$4)   | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2011/11/18<br>12:54 |
| S83 | 5 | electroless and electroplat\$4 and copper and cataly\$4 with electroless and cataly\$4 with(Poly\$4 or adhes\$4) and circuit\$4 near(board or integrat\$4)  | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2011/11/18<br>12:54 |
| S84 | 5 | electroless and electroplat\$4 and copper and (platinum or palladium or cataly\$4) with electroless and (platinum or palladium or cataly\$4) with(Poly\$4 or adhes\$4) and circuit\$4 near (board or integrat\$4) | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2011/11/18<br>12:55 |



|     |     |  |  |    |    |                  |
|-----|-----|--|--|----|----|------------------|
| S85 | 5   | electroless and electroplat\$4 and (platinum or palladium or cataly\$4) with electroless and (platinum or palladium or cataly\$4) with(Poly \$4 or adhes\$4) and circuit\$4 near(board or integrat\$4) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2011/11/18 12:57 |
| S86 | 7   | electroless and electroplat\$4 and (platinum or palladium or cataly\$4) with electroless and (platinum or palladium or cataly\$4) with(Poly \$4 or adhes\$4)   | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2011/11/18 12:57 |
| S87 | 12  | electroless and electroplat\$4 and (platinum or palladium or cataly\$4) with(Poly \$4 or adhes\$4)   | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2011/11/18 13:00 |
| S88 | 12  | electroless and electroplat\$4 and (platinum or palladium or cataly\$4) with(Poly \$4 or adhes\$4)   | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2011/11/18 13:00 |
| S89 | 819 | electroless and (electrodeposit\$4 or electroplat\$4) and (platinum or palladium or cataly\$4) with(Poly \$4 or adhes\$4)  | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2011/11/18 13:03 |
| S90 | 389 | electroless and (electrodeposit\$4 or electroplat\$4) and (platinum or palladium or cataly\$4) with(Poly \$4 or adhes\$4)and (platinum or palladium or cataly\$4)with electroless                      | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2011/11/18 13:03 |



|     |     |  |  |    |    |                  |
|-----|-----|--|--|----|----|------------------|
| S91 | 203 | electroless and (electrodeposit\$4 or electoplat\$4) and (platinum or palladium or cataly\$4) with(Poly \$4 or adhes\$4)and (platinum or palladium or cataly\$4)with electroless and circuit near(board or integrat \$4) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2011/11/18 13:04 |
| S92 | 145 | electroless and (electrodeposit\$4 or electoplat\$4) and (platinum or palladium or cataly\$4) with(adhes \$4)and(platinum or palladium or cataly\$4) with electroless and circuit near(board or integrat\$4)             | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2011/11/18 13:06 |
| S93 | 114 | electroless and (electrodeposit\$4 or electoplat\$4) and (cataly\$4) with(adhes \$4)and(cataly\$4)with electroless and circuit near(board or integrat \$4)   | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2011/11/18 13:06 |
| S94 | 26  | electroless and (electrodeposit\$4 or electoplat\$4) and (cataly\$4) with(adhes \$4)and(cataly\$4)with electroless and circuit near(board or integrat \$4)and substrate with glass and substrate with rough\$4           | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2011/11/18 13:10 |
| S95 | 3   | electroless and (electrodeposit\$4 or electoplat\$4) and (cataly\$4) with(adhes \$4)and(cataly\$4)with electroless and circuit near(board or integrat \$4)and substrate with glass and substrate with roughn\$4          | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2011/11/18 13:11 |



|     |    |  |   |    |    |                     |
|-----|----|--|---|----|----|---------------------|
| S96 | 26 | electroless and (electrodeposit\$4 or electoplat\$4) and (cataly\$4) with(adhes \$4)and(cataly\$4)with electroless and circuit near(board or integrat \$4)and substrate with glass and (glass or substrate) with rough \$4 | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2011/11/18<br>13:13 |
| S97 | 2  | 10/580953  | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2011/11/18<br>18:15 |
| S98 | 38 | stamp\$4 with release same photoresist   | US-PGPUB;<br>USPAT;<br>USOCR; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2011/11/18<br>18:47 |

11/ 18/ 2011 9:22:23 PM

C:\ Documents and Settings\ ttadayyoneslami\ My Documents\ EAST\ Workspaces  
\ 10580953-.wsp